AMENDMENTS TO THE CLAIMS

The following listing of claims replaces all prior versions, and listings, of claims in the application:

1. (Previously presented) A method of managing radiation, the method comprising:

providing a semiconducting device having a two-dimensional carrier gas, wherein the semiconducting device comprises at least one of: a heterodimensional diode, a field effect transistor array, a heterodimensional diode array, and an array of rectifying contacts;

exciting the carrier gas by shining a laser pulse having a duration of approximately one femtosecond to ten picoseconds onto the semiconducting device; and

adjusting a frequency of the radiation using a voltage applied to the semiconducting device.

- (Original) The method of claim 1, wherein the radiation comprises at least one of: terahertz radiation and microwave radiation.
- (Original) The method of claim 1, wherein the adjusting step adjusts at least one of: a gate bias voltage, and a drain bias voltage.

Claims 4-6 (Canceled)

7. (Original) The method of claim 1, wherein the exciting step includes shining the laser pulse onto at least one of: a top side and a bottom side of the semiconducting device. 8. (Previously presented) A method of generating radiation using a field effect transistor, the method comprising:

shining a laser pulse onto at least one of: a gate-source spacing, a gate, a gate-drain spacing, and a substrate of the field effect transistor; and

adjusting a frequency of the radiation by adjusting a carrier density of carriers in a channel of the field effect transistor, wherein the adjusting step includes adjusting a gate length for the gate.

9. (Canceled)

10. (Previously presented) A method of generating radiation using a field effect transistor, the method comprising:

shining a laser pulse onto the field effect transistor; and

adjusting a frequency of the radiation by adjusting a carrier density of carriers in a channel of the field effect transistor, wherein the field effect transistor comprises a transparent gate, and wherein the laser pulse is shone onto the transparent gate.

11. (Previously presented) A method of generating radiation using a field effect transistor, the method comprising:

shining a laser pulse onto the field effect transistor; and

adjusting a frequency of the radiation by adjusting a carrier density of carriers in a channel of the field effect transistor, wherein the adjusting step uses a bias voltage applied to a periodic grating gate of the field effect transistor.

12. (Canceled)

13. (Previously presented) A method of generating radiation using a field effect transistor, the method comprising:

shining a laser pulse onto at least one of: a gate-source spacing, a gate, a gate-drain spacing, and a substrate of the field effect transistor; and

adjusting a frequency of the radiation by adjusting a carrier density of carriers in a channel of the field effect transistor, wherein the radiation comprises at least one of: terahertz radiation and microwave radiation.

14. (Previously presented) A method of generating radiation using a field effect transistor, the method comprising:

shining a laser pulse onto at least one of: a gate-source spacing, a gate, a gate-drain spacing, and a substrate of the field effect transistor; and

adjusting a frequency of the radiation by adjusting a carrier density of carriers in a channel of the field effect transistor, wherein the laser pulse has a duration of approximately one femtosecond to ten picoseconds.

15. (Previously presented) A method of generating radiation using a heterodimensional diode, the method comprising:

shining a laser pulse onto at least one of a top side and a bottom side of the heterodimensional diode; and adjusting a frequency of the radiation using a voltage applied to the heterodimensional diode to adjust a frequency of a plasma wave in a two-dimensional carrier gas in the heterodimensional diode.

16. (Original) The method of claim 15, further comprising adjusting the frequency of the radiation by using a plurality of heterodimensional diodes.

17. (Original) The method of claim 15, further comprising shining a second laser pulse onto a substrate of the heterodimensional diode.

- 18. (Canceled)
- 19. (Canceled)
- 20. (Original) The method of claim 15, wherein the heterodimensional diode includes at least one ohmic contact and at least one rectifying contact.
- 21. (Previously presented) A method of managing radiation, the method comprising: providing a field effect transistor having a two-dimensional carrier gas and a periodic grating gate;

exciting the carrier gas using a laser pulse having a duration of approximately one femtosecond to ten picoseconds; and

adjusting a frequency of the radiation using a voltage applied to the field effect transistor.

- 22. (Canceled)
- 23. (Previously presented) The method of claim 1, wherein the duration of the laser pulse comprises approximately twenty femtoseconds.
- 24. (Previously presented) The method of claim 1, wherein a photon energy of the laser pulse exceeds 1.42 electron Volts.
- 25. (Previously presented) The method of claim 15, wherein the laser pulse has a duration of approximately one femtosecond to ten picoseconds.
- 26. (Previously presented) The method of claim 15, wherein the radiation comprises at least one of: terahertz radiation and microwave radiation.
- 27. (New) A method of generating radiation using a heterodimensional diode, the method comprising:

shining a laser pulse onto at least one of a top side and a bottom side of the heterodimensional diode; and

adjusting a frequency of the radiation using a voltage applied to the heterodimensional diode, wherein the adjusting step comprises adjusting a width of a depletion region formed in the active layer.

28. (New) A method of managing radiation, the method comprising:

providing a field effect transistor having a two-dimensional carrier gas and a periodic grating gate;

exciting the carrier gas using a laser pulse having a duration of approximately one femtosecond to ten picoseconds; and

adjusting a frequency of the radiation using a voltage applied to the field effect transistor, wherein the radiation comprises at least one of: terahertz radiation and microwave radiation.